| L Number | Hits | Search Text | DB | Time stamp |
|----------|--------|---|-------|------------------|
| 1 | 1 | ("6190988").PN. | USPAT | 2004/04/13 17:22 |
| - | 3 | (bottle adj trench) and (bottle adj shaped adj trenches) and DRAM | USPAT | 2004/04/13 16:30 |
| _ | 1 | DICALT | USPAT | 2004/04/13 16:37 |
| _ | i | | USPAT | 2004/04/13 16:25 |
| | 1 | | USPAT | 2004/04/13 16:25 |
| | 1 | | USPAT | 2004/04/13 16:26 |
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| - | | | USPAT | 2004/04/13 16:28 |
| - | ! | | USPAT | 2004/04/13 16:29 |
| • | 1 | | USPAT | 2004/04/13 16:29 |
| | 3 | ((bottle adj trench) and (bottle adj shaped adj trenches) and | USPAT | 2004/04/13 16:37 |
| | | DRAM) and (memory or hard or mask or substrate or | | |
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| 1 | | or isolation or Isolator or shield or polysilicon or lower or | | |
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| | | or parts or removing or etch or etching or silicon or nitride | | i |
| | | or dopant or doped or CVD or thermal or treatment or | | |
| | | anisotropic or expose or exposed) | | |
| | 1 | ("5658816").PN. | USPAT | 2004/04/13 16:37 |
| | 3 | (((bottle adj trench) and (bottle adj shaped adj trenches) and | USPAT | 2004/04/13 16:38 |
| i | | DRAM) and (memory or hard or mask or substrate or | | |
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| | | or dopant or doped or CVD or thermal or treatment or | 1 | |
| | | anisotropic or expose or exposed)) and (memory or hard or | | |
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| | 1 | ("5629226").PN. | USPAT | 2004/04/13 16:38 |
| 1 | 1 | (("5629226").PN.) and (memory or hard or mask or | USPAT | 2004/04/13 16:41 |
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| | 1 | ("6313008").PN. | USPAT | 2004/04/13 16:41 |
| | 1 | ((("5629226").PN.) and (memory or hard or mask or | USPAT | 2004/04/13 16:50 |
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| - | 1 ("6232171").PN. | USPAT | 2004/04/13 16:50 |
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| - | 1 (("6232171").PN.) and (memory or hard or mask or | USPAT | 2004/04/13 17:22 |
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